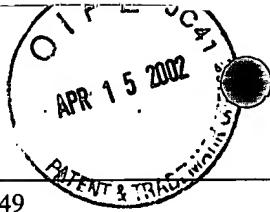
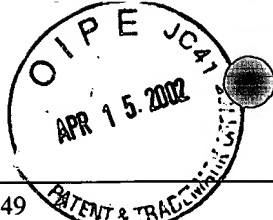


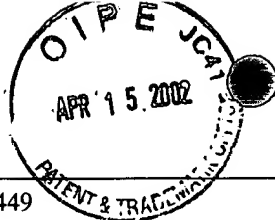
Form PTO 1449 (Rev. 2-32) U.S. Department of Commerce Patent and Trademark Office				Atty. Docket No. LMPY-9220		Serial No.: 09/771,366	
Information Disclosure Statement by Applicant				Applicant: Dirk Basting, et al.			
(Use several sheets if necessary)				Filed: January 15, 2001 Group: <del>2881</del> 2828			
U.S. Patent Documents							
Init.		Document No.	Date	Name	Class	Subclass	Filing Date
<i>JS</i>		3,471,800	10/07/69	Congleton, et al.	331	94.5	12/17/64
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Examiner <i>JS</i> <i>LEPPER</i> <i>Boon</i>					Date Considered <i>9/4/2003</i>		
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		5,051,558	09/24/91	Sukhman	219	121.68	03/20/89
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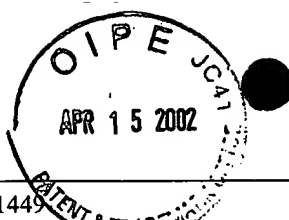
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Examiner: <i>J. P. R. Z. B. N.</i>					Date Considered: <i>9/4/2003</i>		
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J3		5,978,406	11/02/99	Rokni, et al.	372	58	01/30/98	
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J3		6,327,290	12/04/01	Govorkov, et al.	372	61	06/14/00	
		6,345,065	02/05/02	Kleinschmidt, et al.	372	57	05/24/99	
Foreign Documents								
Translation								
Init.		Document No.	Date	Country	Class	Subclass	Yes	No
J3		44-8147	1969	Japan	100	D0		X
		60-205420	10/17/85	Japan	G02B	27/00	Abstract	
		8-274399	11/18/86	Japan	H04S	3/104	X	
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Foreign Documents								
							Translation	
Init.		Document No.	Date	Country	Class	Subclass	Yes	No
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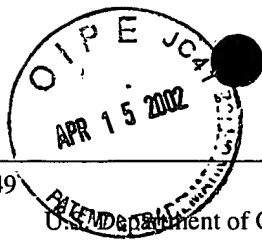
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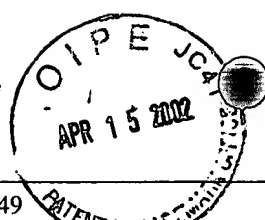


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Information Disclosure Statement by Applicant		Applicant: Dirk Basting, et al.	
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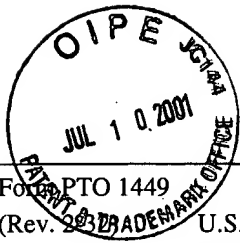


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Information Disclosure Statement by Applicant			Applicant: Dirk Basting, et al.	
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<b>U.S. Patent Documents</b>																	
Init.		Document No.	Date	Name	Class	Subclass	Filing Date										
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